

Special Equipment Recharge Rates

Name	Description	Price	Unit
aln2	Tegal Endeavor AT sputter dep	\$0.82	minute
aln2	Tegal Endeavor AT sputter dep	\$0.86	minute
amatepi	epitaxial silicon / germanium de	\$0.82	minute
amatepi	epitaxial silicon / germanium de	\$0.86	minute
amst	AMST Molecular Vapor Depositi	\$0.82	minute
amst	AMST Molecular Vapor Depositi	\$0.86	minute
asap-liftoff	Liftoff System - Model ASAP LO	\$0.84	minute
asap-liftoff	Liftoff System - Model ASAP LO	\$0.88	minute
asiq	Tencor AS500 Profilometer	\$0.82	minute
asiq	Tencor AS500 Profilometer	\$0.86	minute
asml300	ASML 5500/300 DUV Stepper	\$0.82	minute
asml300	ASML 5500/300 DUV Stepper	\$0.86	minute
cambridge	Cambridge Fiji F200 Plasma AL	\$0.82	minute
cambridge	Cambridge Fiji F200 Plasma AL	\$0.86	minute
canon	Canon 4X wafer stepper	\$0.82	minute
canon	Canon 4X wafer stepper	\$0.86	minute
centura-3-5	Centura Compound Etch - Char	\$0.82	minute
centura-3-5	Centura Compound Etch - Char	\$0.86	minute
centura-met	Centura DPS Metal Etcher - Ch	\$0.82	minute
centura-met	Centura DPS Metal Etcher - Ch	\$0.86	minute
centura-mxp	Centura oxide etch chamber - C	\$0.82	minute
centura-mxp	Centura oxide etch chamber - C	\$0.86	minute
cha	CHA E-beam Evaporator	\$0.82	minute
cha	CHA E-beam Evaporator	\$0.86	minute
cmp	Strausbaugh CMP	\$0.82	minute
cmp	Strausbaugh CMP	\$0.86	minute
compound-ox	Table Top Wet-Oxidation Furna	\$0.82	minute
compound-ox	Table Top Wet-Oxidation Furna	\$0.86	minute
cpd	Tousimis 915B 6" Critical Point I	\$0.82	minute
cpd	Tousimis 915B 6" Critical Point I	\$0.86	minute
cpd2	Tousimis 815A 1.5" Critical Poin	\$0.82	minute
cpd2	Tousimis 815A 1.5" Critical Poin	\$0.86	minute
crestec	Crestec EBEAM Lithography	\$1.81	minute
crestec	Crestec EBEAM Lithography	\$2.02	minute
dektak	Dektak Model 3030 Surface Pro	\$0.82	minute
dektak	Dektak Model 3030 Surface Pro	\$0.86	minute
disco	Disco DAD3240 Automated Dici	\$0.82	minute
disco	Disco DAD3240 Automated Dici	\$0.86	minute
ebeam1	Electron Beam 10 kW 4-pocket	\$0.82	minute
ebeam1	Electron Beam 10 kW 4-pocket	\$0.86	minute
edwards	Edwards Sputter System	\$0.82	minute
edwards	Edwards Sputter System	\$0.86	minute
edwardseb3	Edwards 306 E-Beam System	\$0.82	minute

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Name	Description	Price	Unit
edwardseb3	Edwards 306 E-Beam System	\$0.86	minute
edx	Energy-dispersive X-ray Spectro	\$0.82	minute
edx	Energy-dispersive X-ray Spectro	\$0.86	minute
fei-sem	FEI Nova NanoSEM650	\$1.18	minute
fei-sem	FEI Nova NanoSEM650	\$1.31	minute
flexus	Tencor FleXus FLX2320 Stress	\$0.82	minute
flexus	Tencor FleXus FLX2320 Stress	\$0.86	minute
flipchip	Suss FC150	\$0.82	minute
flipchip	Suss FC150	\$0.86	minute
gartek	Gartek sputterer	\$65.00	4 hours
gcapg	GCA 3600 pattern generator	\$0.82	minute
gcapg	GCA 3600 pattern generator	\$0.86	minute
gcaws2	GCA G-Line 10X Wafer Stepper	\$0.82	minute
gcaws2	GCA G-Line 10X Wafer Stepper	\$0.86	minute
gcaws6	GCA 8500 5X I-line	\$0.82	minute
gcaws6	GCA 8500 5X I-line	\$0.86	minute
gnpcmp	G&P Poli 500 CMP	\$0.82	minute
gnpcmp	G&P Poli 500 CMP	\$0.86	minute
ionmill6	Pi Scientific 6" Ion Beam Mill	\$0.82	minute
ionmill6	Pi Scientific 6" Ion Beam Mill	\$0.86	minute
keyence	Recharge digital microscope	\$0.82	minute
keyence	Recharge digital microscope	\$0.86	minute
ksaligner	Karl Suss Mask/Bond Aligner	\$0.82	minute
ksaligner	Karl Suss Mask/Bond Aligner	\$0.86	minute
lacvd	Laser Assisted Chemical Vapor	\$0.82	minute
lacvd	Laser Assisted Chemical Vapor	\$0.86	minute
lam6	Lam 4526 Oxide Etch	\$0.82	minute
lam6	Lam 4526 Oxide Etch	\$0.86	minute
lam7	Lam Research 9626 Aluminum I	\$0.82	minute
lam7	Lam Research 9626 Aluminum I	\$0.86	minute
lam8	9426 Lam Research TCP MOS	\$0.82	minute
lam8	9426 Lam Research TCP MOS	\$0.86	minute
matrix-etch	Matrix 303 plasma etcher	\$0.82	minute
matrix-etch	Matrix 303 plasma etcher	\$0.86	minute
mrc944	MRC Sputtering System with Sp	\$0.72	minute
nanotube	Nanotube Furnace	\$0.82	minute
nanotube	Nanotube Furnace	\$0.86	minute
olympus	Olympus LEXT 3D Laser Measu	\$0.82	minute
olympus	Olympus LEXT 3D Laser Measu	\$0.86	minute
oxford	Oxford Plasmalab System 100	\$0.82	minute
oxford	Oxford Plasmalab System 100	\$0.86	minute
oxford-icp	Oxford Instruments PlasmaPro1	\$0.82	minute
oxford-icp	Oxford Instruments PlasmaPro1	\$0.86	minute

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Name	Description	Price	Unit
oxford2	Oxford Plasmalab 80 PECVD	\$0.82	minute
oxford2	Oxford Plasmalab 80 PECVD	\$0.86	minute
oxfordpvd2	Oxford Cluster Chamber2 Sputt	\$0.82	minute
oxfordpvd2	Oxford Cluster Chamber2 Sputt	\$0.86	minute
parylene	Specialty Coating Systems PDS	\$0.82	minute
parylene	Specialty Coating Systems PDS	\$0.86	minute
picosun	Picosun Sunale R150 ALD	\$0.82	minute
picosun	Picosun Sunale R150 ALD	\$0.86	minute
plotter	Hewlett Packard Wide Plotter	\$50.00	each
pqecr	Plasma Quest ECR PECVD	\$0.82	minute
pqecr	Plasma Quest ECR PECVD	\$0.86	minute
primaxx	Primaxx SPTS uEtch HF Vapor	\$10.20	hour
ptherm	Plasmatherm reactive ion etche	\$0.82	minute
ptherm	Plasmatherm reactive ion etche	\$0.86	minute
randex	Randex sputtering system	\$65.00	4 hours
rtp1	AccuThermo AW610 RTP for III,	\$0.82	minute
rtp1	AccuThermo AW610 RTP for III,	\$0.86	minute
rtp2	AccuThermo AW610 RTP III/V -	\$0.82	minute
rtp2	AccuThermo AW610 RTP III/V -	\$0.86	minute
rtp3	AccuThermo AW610 RTP Si No	\$0.82	minute
rtp3	AccuThermo AW610 RTP Si No	\$0.86	minute
rtp4	AccuThermo AW610 RTP Si MC	\$0.82	minute
rtp4	AccuThermo AW610 RTP Si MC	\$0.86	minute
rtp8	AccuThermo AW810 RTP Si MC	\$0.82	minute
rtp8	AccuThermo AW810 RTP Si MC	\$0.86	minute
sca	Surface Charge Analyser	\$0.82	minute
sca	Surface Charge Analyser	\$0.86	minute
semi	Semigroup plasma etcher	\$0.82	minute
semi	Semigroup plasma etcher	\$0.86	minute
sopra	Sopra Variable Angle/Frequency	\$0.82	minute
sopra	Sopra Variable Angle/Frequency	\$0.86	minute
sp3	sp3 CVD Diamond Coating Syst	\$5.10	hour
sts-oxide	APS deep oxide etch	\$0.82	minute
sts-oxide	APS deep oxide etch	\$0.86	minute
sts2	ICP pulsed gas deep silicon etcl	\$0.82	minute
sts2	ICP pulsed gas deep silicon etcl	\$0.86	minute
svgcoat1	SVG 8600 6" Coat & Bake (fron	\$0.82	minute
svgcoat1	SVG 8600 6" Coat & Bake (fron	\$0.86	minute
svgcoat2	SVG 8600 4" Coat & Bake (rear	\$0.82	minute
svgcoat2	SVG 8600 4" Coat & Bake (rear	\$0.86	minute
svgcoat3	SVG 8600 6" LOR & BARC Coa	\$0.82	minute
svgcoat3	SVG 8600 6" LOR & BARC Coa	\$0.86	minute
svgcoat6	SVG8800 6" Coat Track	\$0.82	minute

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svgcoat6	SVG8800 6" Coat Track	\$0.86	minute
svgdev1	SVG8600 6" Develop Track	\$0.82	minute
svgdev1	SVG8600 6" Develop Track	\$0.86	minute
svgdev2	SVG8600 4" Develop Track	\$0.82	minute
svgdev2	SVG8600 4" Develop Track	\$0.86	minute
svgdev6	SVG8800 6" Develop Track	\$0.82	minute
svgdev6	SVG8800 6" Develop Track	\$0.86	minute
tescal	Technical Eningeering Services	\$0.82	minute
tescal	Technical Eningeering Services	\$0.86	minute
topgun	3 target RF DC co-sputtering sy	\$0.82	minute
topgun	3 target RF DC co-sputtering sy	\$0.86	minute
tystar1	Tystar 6" Wet/Dry Oxidation	\$0.82	minute
tystar1	Tystar 6" Wet/Dry Oxidation	\$0.86	minute
tystar10	Tystar LPCVD Doped Poly	\$0.82	minute
tystar10	Tystar LPCVD Doped Poly	\$0.86	minute
tystar11	Tystar LPCVD Doped LTO	\$0.82	minute
tystar11	Tystar LPCVD Doped LTO	\$0.86	minute
tystar12	Tystar Doped LTO	\$0.82	minute
tystar12	Tystar Doped LTO	\$0.86	minute
tystar13	Tystar 6" POCL3	\$0.82	minute
tystar13	Tystar 6" POCL3	\$0.86	minute
tystar14	Tystar 6" Solid-Source Boron	\$0.82	minute
tystar14	Tystar 6" Solid-Source Boron	\$0.86	minute
tystar15	Tystar 6" LPCVD Silicon Carbide	\$0.82	minute
tystar15	Tystar 6" LPCVD Silicon Carbide	\$0.86	minute
tystar16	Tystar 6" Doped Poly LPCVD	\$0.82	minute
tystar16	Tystar 6" Doped Poly LPCVD	\$0.86	minute
tystar17	Tystar LPCVD Low Stress Nitrid	\$0.82	minute
tystar17	Tystar LPCVD Low Stress Nitrid	\$0.86	minute
tystar18	Tystar 6" MOS Sinter	\$0.82	minute
tystar18	Tystar 6" MOS Sinter	\$0.86	minute
tystar19	Tystar LPCVD Si/Ge, MOS	\$0.82	minute
tystar19	Tystar LPCVD Si/Ge, MOS	\$0.86	minute
tystar2	Tystar 6" Wet/Dry Oxidation	\$0.82	minute
tystar2	Tystar 6" Wet/Dry Oxidation	\$0.86	minute
tystar20	Tystar Si/Ge LPCVD for MEMS	\$0.82	minute
tystar20	Tystar Si/Ge LPCVD for MEMS	\$0.86	minute
tystar3	Tystar 6" Wet/Dry Oxidation	\$0.82	minute
tystar3	Tystar 6" Wet/Dry Oxidation	\$0.86	minute
tystar4	Tystar 6" Wet/Dry Oxidation	\$0.82	minute
tystar4	Tystar 6" Wet/Dry Oxidation	\$0.86	minute
tystar5	Tystar 200mm Wet/Dry Oxidatio	\$0.82	minute
tystar5	Tystar 200mm Wet/Dry Oxidatio	\$0.86	minute

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Name	Description	Price	Unit
tystar6	Tystar 200mm N-Type Doping	\$0.82	minute
tystar6	Tystar 200mm N-Type Doping	\$0.86	minute
tystar7	Tystar 200mm P-Type Doping	\$0.82	minute
tystar7	Tystar 200mm P-Type Doping	\$0.86	minute
tystar9	Tystar LPCVD Nitride	\$0.82	minute
tystar9	Tystar LPCVD Nitride	\$0.86	minute
ultek2	Ultek2 Angled Cooled Chuck E-	\$0.82	minute
ultek2	Ultek2 Angled Cooled Chuck E-	\$0.86	minute
westbond	West Bond 7400B Al wire bond	\$0.82	minute
westbond	West Bond 7400B Al wire bond	\$0.86	minute
westbond2	West Bond 7400B Au wire bond	\$0.82	minute
westbond2	West Bond 7400B Au wire bond	\$0.86	minute
wyko	Wyko Optical Profilometer	\$0.82	minute
wyko	Wyko Optical Profilometer	\$0.86	minute
xdif	X-Ray Diffractometer	\$0.82	minute
xdif	X-Ray Diffractometer	\$0.86	minute
xetch	XeF2 Bulk Silicon Etcher	\$0.82	minute
xetch	XeF2 Bulk Silicon Etcher	\$0.86	minute
zeiss-sem	Zeiss Scanning Electron Micros	\$0.82	minute
zeiss-sem	Zeiss Scanning Electron Micros	\$0.86	minute